

### Amendments to Specification

Please change the title of the invention as follow:

-- METHOD OF MANUFACTURING APERTURE PLATE --

Please change paragraph [0001] as follows:

[0001] The invention relates to a ~~coating~~ method and of manufacturing an aperture plate or diaphragm, more particularly, a ~~coating~~ method suitable for manufacturing an aperture plate with a high precision to be used for an electron beam apparatus, such as an electron microscope, ~~and an aperture plate coated by the coating method.~~

Please change paragraphs [0012] and [0013] as follows:

[0012] An object of the present invention is to solve the problems in the conventional techniques as described above and to provide a ~~coating~~ method of manufacturing an aperture plate, wherein a good repeatability can be obtained.

[0013] Another object of the invention is to provide a ~~coating~~ method of manufacturing an aperture plate, wherein an electrically conductive amorphous coating having a high density and purity can be formed to an interior of a micro-hole, and an aperture plate with such high quality coating can be produced.

Please change paragraph [0015] as follows:

[0015] The present invention provides a method ~~for coating~~ of manufacturing an aperture plate or diaphragm that is used for an electron beam apparatus. More specifically, the ~~coating~~ method includes a step of adding a hydrogen gas to a sublimation gas consisting of an osmium oxide in the plasma excitation chemical vapor deposition (CVD) when an osmium coating is applied to a metal plate with a micro-hole.